

High-frequency SiGe-n-MODFET for microwave applications

M. Zeuner, T. Hackbarth, G. Hock, D. Behammer and U. König. "High-frequency SiGe-n-MODFET for microwave applications." 1999 Microwave and Guided Wave Letters 9.10 (Oct. 1999 [MGWL]): 410-412.

n-type SiGe modulation-doped hetero field-effect transistors (MODFET's) with a 0.25- μm Schottky-gate on a Si/sub 0.55/Ge/sub 0.45/ buffer are presented. The layer structure was designed to enable elevated sheet carrier densities of $n_s = 7.0 \times 10^{12} \text{ cm}^{-2}$ at moderate electron mobilities of 1050 cm^2/Vs . Reducing the thickness of the cap layers enhances the control of the gate on the 2DEG and leads to a high transconductance of 320 mS/mm . Targeting analog applications, we focused on large current densities around 400 mA/mm . Due to advanced RF-characteristics the 100-GHz hurdle of f_{max} was passed for the first time with $f_{\text{max}}(U) = 120 \text{ GHz}$ and f_{t} was determined at 42 GHz.

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